

## **REMARKS**

Claims 1-13 were pending when last examined, all of which stand rejected. Claims 1, 4, 5, 8, 10, and 13 are amended.

### **Claim Rejections – 35 USC § 103**

Claims 1-13 are rejected under 35 USC § 103(a) as being unpatentable over U.S. Patent No. 6,933,533 to Yamazaki et al. (“Yamazaki”) in view of U.S. Published Patent Application No. 2005/0038276 to Laxman et al (“Laxman”).

Independent Claims 1, 5, and 10 are patentable over Yamazaki and Laxman at least because they recite “... a chemical vapor deposition insulating film having a low dielectric constant and a thickness of about 1  $\mu$ m or more ....” Pages 3-4 of the Office Action state that “absent any showing of criticality, specific dimensions of layer thickness and overlap would have been obvious to one having ordinary skill in the art ....” As described in the subject Application, for example on page 8, lines 24-26, the thickness of the chemical vapor deposition insulating film is made to be 1  $\mu$ m or more to secure a vertical interval between the pixel electrode 126 and the metal electrode 134.

In contrast to the claimed invention, Yamazaki teaches forming an insulating film having a thickness of 500 nm (Yamazaki, col. 15, lines 50-53). Thus, if anything, Yamazaki teaches away from the invention.

Dependent claims 2-4, 6-9, and 11-13 are patentable over Yamazaki and Laxman for the same reason Claims 1, 5, and 10 are patentable over Yamazaki and Laxman.

Claims 4, 8, and 13 are patentable also because they recite that “... the chemical vapor deposition insulating film has a thickness more than about 1  $\mu$ m between the first electrode and the organic electroluminescent layer.” Page 8, line 26 to page 9, line 2 of the Application states that “... it is preferred that the CVD insulating film 128 of low dielectric constant is overlapped to more than 1  $\mu$ m with the edge portion of the pixel electrode 126 in order to secure alignment margin of the organic EL layer. This is distinguishable from the teaching in Yamazaki to form an insulating film having a thickness of 500 nm.

Claim 9 is patentable because it recites that “the chemical vapor deposition insulating film and an edge portion of the pixel electrode overlap by more than about 1  $\mu$ m.” The explanation provided for Claims 4, 8, and 13 apply here.

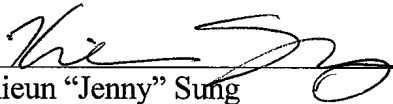
### Conclusion

Based on the foregoing reasons, Claims 1-13 are now in condition for allowance. Please telephone the undersigned attorney at (408) 392-9250 if there are any questions.

Respectfully submitted,

MACPHERSON KWOK CHEN & HEID LLP

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By   
Kieun "Jenny" Sung  
Attorney for Applicant  
Reg. No. 48,639

MACPHERSON KWOK CHEN & HEID LLP  
2033 Gateway Place, Ste. 400  
San Jose, CA 95110  
Telephone: (408) 392-9250  
Facsimile: (408) 392-9262